

Nov. 10, 2005

IEUVI Contamination TWG meeting, San Diego

IEUVI Resist TWG meeting

ASET update

ASET EUV Process Technology Laboratory
Iwao Nishiyama

ASET Update

Exposure tool

■ HiNA-3

- Activity was shifted from Tool evaluation phase to Resist evaluation

■ MET of Berkeley

- Start to use Berkeley MET
- Purposes are
 - learning on Exposure tool
 - Use programmable illuminator
 - Calibration on photosensitivity

Resist Evaluation

- Collaboration with Resist suppliers
- Search CA resists which has 30 nm resolution
- Molecular resist evaluation with NEDO foundation
- LER evaluation
- Outgas evaluation using newly completed apparatus

Outgas Evaluation Apparatus at SBL-2 of Super ALIS

